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Richard Van Court Carr, et al..

FILING DATE

GROUP

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

EXAM- DER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
PR	0 0 5 9 7 1 0	3/27/2003	Inoue	430	270.1	
PR	0 0 0 4 5 7 0	1/10/2002	A. Zampini, et al.	526	257	2/23/2001
PR	0 0 5 1 9 3 6	5/2/2002	Y. Harada, et al.	430	270.1	9/7/2001
PR	0 0 5 5 0 6 0	5/9/2002	G. N. Taylor, et al.	430	270.1	9/8/2001
PR	0 0 6 1 4 6 4	5/23/2002	T. Aoi, et al.	430	270.1	9/25/2001
PR	6 2 9 1 1 3 0	9/18/2001	K. Kodama, et al.	430	270.1	7/27/1999
PR	6 4 0 6 8 2 8	6/18/2002	C. R. Szmanda, et al.	430	270.1	2/24/2000

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
PR	JP	2	1	7	9	7	3	1	7/2003	Japan (Abstract)			X	
PR	WO	0	2	3	1	5	9	5	4/2003	World	G03F	7/00	X	
PR	EP	1	1	0	3	8	5	6	5/2001	Europe	G03F	7/039	X	
PR	EP	1	1	2	6	3	2	2	8/2001	Europe	G03F	7/039	X	
PR	WO	0	0	1	7	7	1	2	8/2003	World	G03F	7/039	X	
PR	WO	0	0	6	7	0	7	2	11/2000	World	G03F	7/004	X	
PR	WO	0	1	6	3	3	6	2	8/2001	World	G03F	7/00	X	
PR	WO	0	1	8	5	8	1	1	11/2001	World	G03F	7/00	X	
PR	WO	0	2	2	1	2	1	2	3/2002	World	G03F	7/004	X	
PR	WO	0	2	2	1	2	1	3	3/2002	World	G03F	7/004	X	
PR	WO	0	2	2	1	2	1	4	3/2002	World	G03F	7/004	X	
PR	WO	0	2	2	1	2	1	6	3/2002	World	G03F	7/039	X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

PR	Hiroshi Ito, et al., "Synthesis and Evaluation of Alicyclic Backbone Polymers for 193 nm Lithography", American Chemical Society, 1998.
PR	Hiroshi Ito, et al., "Aliphatic Platforms for the Design of 157 nm Chemically Amplified Resists", SPIE Proceedings, Vol. 4690 (2002), 18-28.
PR	M. M. Dhangra, et al., "Polymerization of 1,1,1-Trifluoroacetone with Aliphatic Secondary Amines. A Proton and Fluorine Magnetic Resonance Investigation," Organic Magnetic Resonance, Vol. 9, No. 1 (1977), pp. 23-28.
PR	H. E. Simmons, et al., "Fluoroketones" The Central Research Department Station, E. I. du Pont de Nemours and Co., Vol. 82 (1959), pp. 2288-2296.
PR	E. T. McBee, et al., "The Chemistry of 1,1,1-Trifluoropropanone. II. The Reactions of 4-Methyl-1,1,1,5,5,5-hexafluoro-3-penten-2-one with Methymagnesium Iodide," The Department of Chemistry, Purdue University (1956), pp. 4597-4598.
PR	A. L. Henne, et al., "Trifluoromethylated Butadienes," The Department of Chemistry at The Ohio State University (1954), pp. 5147-5148.
PR	K. J. Pryzbilla, et al., "Hexafluoroacetone in Resist Chemistry: A Versatile New Concept for Materials for Deep UV Lithography," SPIE Advances in Resist Chemistry and Process IX Vol. 1672 (1992).
PR	M. K. Crawford, et al., "New Materials for 157 nm Photoresists: Characterization and Properties," SPIE Advances in Resist Chemistry and Processing IX Vol. 3999 (2000).
PR	R. R. Dammel, et al., "New Resin Systems for 157 nm Lithography," Journal of Photopolymer Science and Technology, Vol. 14 No. 4 (2001).
PR	H. Ito, et al., "Development of 157 nm Positive Resists," J. Vac. Sci. Technol. B 19(6) (2001).
PR	H. Ito, "Dissolution Behavior of Chemically Amplified Resist Polymers for 248-, 193-, and 157-nm Lithography," J. Res. & Dev. Vol. 45 No. 5 (2001).
PR	S. Cho, et al., "Investigation of a Fluorinated ESCAP based resist for 157 nm Lithography," (2001).
PR	K. Patterson, et al., "The Challenges in Materials Design for 157 nm Photoresists," Lithography, Solid State Technology, pp. 41-48 (2000).

EXAMINER

R. Key

DATE CONSIDERED

4/15/06

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.